

ABSTRACT

A main control system 20 determines the mode of focusing control based on the both data representing the surface condition of the divided area and the data for the shape of the illumination area on the wafer W. Then, the main control system 20 controls the actuators 21A, 22A and 23A based on the detection result from the focus sensor 7, and performs the focusing control of the substrate stage 10 for holding the wafer W through to the projection optical system PL. Simultaneously with the focusing control, the main control system controls the wafer stage driving block 16 to perform the synchronous moving of the reticle stage 3 and the substrate table through projection optical system PL. Thereby the patterns formed on the reticle R is transferred onto the divided area on the wafer W. Not premising the high focusing control driving practicability, the pattern is transferred onto the substrate without serious deterioration of the imaging performance.

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